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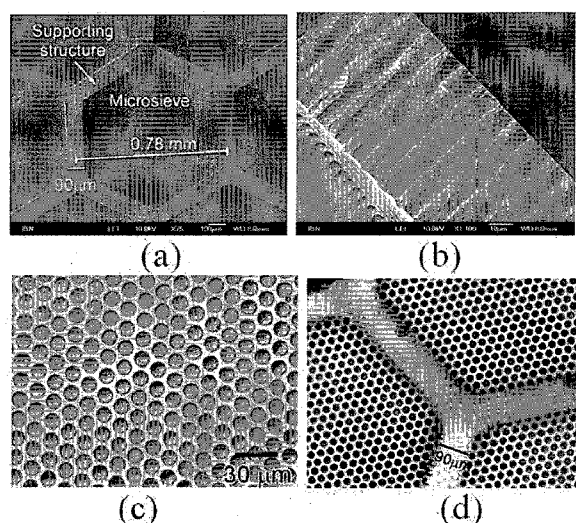


Fig. 3

(57) Abstract: It is disclosed a microsieve comprising two layers, wherein the first layer is a membrane layer having a plurality of micropores contained therein and a thickness of about 10 μm to about 100 μm, and the second layer is a membrane support layer having a plurality of openings contained therein and a thickness of about 100 μm to about 500 μm, wherein the openings are larger in diameter than the micropores, and wherein at least one of the membrane layer or membrane support layer is formed of a SU-8 photoresist material.

